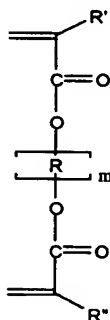


CROSS-LINKING MONOMERS FOR PHOTORESIST, AND PROCESS FOR PREPARING PHOTORESIST POLYMERS USING THE SAME

ABSTRACT OF THE DISCLOSURE

The present invention discloses a cross-linking monomer represented by the following Chemical Formula 1, a process for preparing a photoresist polymer using the same, and said photoresist polymer:

<Chemical Formula 1>



wherein, R' and R'' individually represent hydrogen or methyl; m represents a number of 1 to 10; and R is selected from the group consisting of straight or branched C₁₋₁₀ alkyl, straight or branched C₁₋₁₀ ester, straight or branched C₁₋₁₀ ketone, straight or branched C₁₋₁₀ carboxylic acid, straight or branched C₁₋₁₀ acetal, straight or branched C₁₋₁₀ alkyl including at least one hydroxyl group, straight or branched C₁₋₁₀ ester including at least one hydroxyl group, straight or branched C₁₋₁₀ ketone including at least one hydroxyl group, straight or branched C₁₋₁₀ carboxylic acid including at least one hydroxyl group, and straight or branched C₁₋₁₀ acetal including at least one hydroxyl group.